App. No. 09/894,230

Amendment dated October 27, 2003

Reply to Office action of August 29, 2003

IN THE SPECIFICATION:

Please amend the specification as follows:

Page 7, lines 9-14 (the brief description for Figures 3-5): please replace these

paragraphs with the following rewritten paragraphs:

Figure 3 illustrates a block diagram depicting a developed photoresist

being exposed to an ultraviolet (UV) light in accordance with one embodiment of the

invention.

Figure 4 illustrates a block diagram depicting an etched substrate having

a post-etched hardened top layer of a silicon-containing photoresist.

Figure 5 illustrates a flowchart depicting a method for increasing a

silicon-containing photoresist selectivity in accordance with one embodiment of the

invention.